

| | | | |
|-----------------------------------|---------------------------------------|---|-------------|
| Notice of References Cited | Application/Control No. 09/652,533 | Applicant(s)/Patent Under Reexamination SANDHU ET AL. | |
| | Examiner W. David Coleman | Art Unit 2823 | Page 1 of 1 |

U.S. PATENT DOCUMENTS

| * | | Document Number Country Code-Number-Kind Code | Date MM-YYYY | Name | Classification |
|---|---|--|-----------------|----------------|----------------|
| | A | US-6,174,377 | 01-2001 | Doering et al. | 118/715 |
| | B | US-5,916,365 | 06-1999 | Sherman | 117/92 |
| | C | US- | | | |
| | D | US- | | | |
| | E | US- | | | |
| | F | US- | | | |
| | G | US- | | | |
| | H | US- | | | |
| | I | US- | | | |
| | J | US- | | | |
| | K | US- | | | |
| | L | US- | | | |
| | M | US- | | | |

FOREIGN PATENT DOCUMENTS

| * | | Document Number Country Code-Number-Kind Code | Date MM-YYYY | Country | Name | Classification |
|---|---|--|-----------------|---------|------|----------------|
| | N | | | | | |
| | O | | | | | |
| | P | | | | | |
| | Q | | | | | |
| | R | | | | | |
| | S | | | | | |
| | T | | | | | |

NON-PATENT DOCUMENTS

| * | | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages) |
|---|---|---|
| | U | Suntola, "Surface chemistry of materials deposition at atomic layer level", Applied Surface Science, vol. 100/101, March 1996, pp. 391-398. |
| | V | Aarik et al., "Effect of growth conditions on formation of TiOsub2-II thin films in atomic layer deposition process", Journal of Crystal Growth, Vol. 181, August 1997, pp. 259-264 |
| | W | Skarp, "ALE-reactor for large area depositions", Applied Surface Science, vol. 112, March 1997, pp. 251-254. |
| | X | |

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.